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CS-00-198

November 9, 2001



To: Commissioner of Patents and Trademarks
Washington, D.C. 20231

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TC 1700

Subject:

Serial No. 09/957,424 09/21/01

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WET ABATEMENT SYSTEM FOR WASTE SiH₄

Grp. Art Unit: 1741

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INFORMATION DISCLOSURE STATEMENT

Enclosed is Form PTO-1449, Information Disclosure Citation
In An Application.

The following Patents and/or Publications are submitted to
comply with the duty of disclosure under CFR 1.97-1.99 and
37 CFR 1.56. Copies of each document is included herewith.

U.S. Patent 6,174,349 to DeSantis, "Continuous Effluent
Gas Scrubber System and Method," teaches a wet scrubber in
combination with the burn box.

U.S. Patent 5,955,037 to Holst et al., "Effluent Gas
Stream Treatment System Having Utility for Oxidation Treatment
of Semiconductor Manufacturing Effluent Gases," discloses an
oxidation treatment.

U.S. Patent 5,320,817 to Hardwick et al., "Process for Sorption of Hazardous Waste Products from Exhaust Gas Streams," discloses an amine-forming metal salt to scrub silane.

The following two U.S. Patents describe processes and devices including burn boxes:

- 1) U.S. Patent 6,126,906 to Imamura, "Apparatus for Removing Harmful Components in a Semiconductor Exhaust Gas."
- 2) U.S. Patent 5,183,646 to Anderson et al., "Incinerator for Complete Oxidation of Impurities in a Gas Stream."

Sincerely,



Stephen B. Ackerman,
Reg. No. 37761